

ABSTRACT OF THE DISCLOSURE

An exposure apparatus (EX) that has an exposure region (E) for irradiating exposure light (EL) to a substrate (W) via an optical system (30) and a liquid (LQ) and a measurement region (A) for obtaining information relating to the position of the substrate (W) in advance of exposure and moves the substrate (W) between the exposure region (E) and the measurement region (A) to perform exposure of the substrate (W); comprising a penetration shielding mechanism (60) that prevents the penetration of the gas (G) in the vicinity of the exposure region (E) to the measurement region (A).